

Title (en)
Resist development process

Title (de)
Resistentwicklungsverfahren

Title (fr)
Procédé de développement de photoréserves

Publication
EP 0887710 A3 19990908 (EN)

Application
EP 98109959 A 19980602

Priority
US 88311697 A 19970626

Abstract (en)
[origin: EP0887710A2] A resist development process includes spinning a resist layer while immersing the resist layer in developer.

IPC 1-7
G03F 7/30

IPC 8 full level
G03F 7/30 (2006.01); **H01L 21/027** (2006.01)

CPC (source: EP KR)
G03F 7/0035 (2013.01 - KR); **G03F 7/0045** (2013.01 - KR); **G03F 7/11** (2013.01 - KR); **G03F 7/30** (2013.01 - KR); **G03F 7/3021** (2013.01 - EP);
G03F 7/32 (2013.01 - KR)

Citation (search report)

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EP 0887710 A2 19981230; EP 0887710 A3 19990908; EP 0887710 B1 20030219; CN 1213788 A 19990414; DE 69811430 D1 20030327;
DE 69811430 T2 20031120; JP H11109648 A 19990423; KR 19990006917 A 19990125

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EP 98109959 A 19980602; CN 98108925 A 19980522; DE 69811430 T 19980602; JP 17882198 A 19980625; KR 19980021855 A 19980612